## a 2004 0249

The invention relates to the semiconductor technology, in particular to processes for nanocomposite obtaining. The process for nanocomposite obtaining includes the sensitization and catalytic activation of the surface of a preliminarily obtained porous structure and subsequent filling of the pores with metal. The sensitization and the catalytic activation are carried out in ultrasonic field. The porous structure may be made of semiconductor material.

Claims: 1 Fig.: 1